

WHAT IS CLAIMED IS:

1. A method for forming anti-glare pixel-defining layers on an OLED panel, comprising following steps:
 - (A) providing a substrate;
 - 5 (B) forming a plurality of first electrodes on said substrate;
 - (C) coating a layer of anti-glare compositions comprising at least (1) non-photosensitive polyimide or polyimide precursor and (2) light-absorbing pigments or dyes on said substrate or selectively on said first electrodes;
 - 10 (D) first prebaking said substrate with said layer of said anti-glare compositions;
 - (E) coating a layer of photoresist compositions on said layer of anti-glare compositions;
 - (F) second prebaking said substrate with said anti-glare compositions and said photoresist;
 - 15 (G) forming patterns of said photoresist through exposing said substrate to masked radiation, developing said photoresist on said substrate, etching said layer of said anti-glare compositions and said photoresist at the same time to form patterned layers of said anti-glare polyimide or polyimide precursor compositions and patterned photoresist; wherein said patterns of said photoresist are as same as said patterns of said layers of said anti-glare polyimide or polyimide precursor compositions;
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(H) releasing or stripping said photoresist; and

(I) baking said substrate with said patterned anti-glare polyimide or polyimide precursor compositions for crosslinking or curing said patterned anti-glare polyimide or polyimide precursor compositions to form said anti-glare pixel-defining layers;

5 wherein said patterns of said layer of said anti-glare polyimide or polyimide precursor compositions divide said first electrodes into a plurality of open areas which are not covered by said anti-glare pixel-defining layers.

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2. The method as claimed in claim 1, further comprising forming parallel photoresist ramparts having T-top shape cross-section selectively on said anti-glare polyimide pixel-defining layer, on said first electrodes, or on said substrate.

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3. The method as claimed in claim 1, wherein said substrate with patterned anti-glare polyimide or polyimide precursor compositions is baked at a temperature which is at least higher than 200 °C.

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4. The method as claimed in claim 1, wherein said patterns of said anti-glare pixel-defining layers are parallel stripes and said parallel stripes of anti-glare pixel-defining layers intersect with said first electrodes perpendicularly.

5. The method as claimed in claim 2, wherein said ramparts of photoresist intersect with said first electrodes perpendicularly.

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6. The method as claimed in claim 2, wherein said photoresist of

5 said ramparts is positive photoresist.

7. The method as claimed in claim 1, further comprising (J) forming a plurality of ramparts on said substrate and selectively on said first electrodes or said stripes of said anti-glare polyimide pixel-defining layer; wherein each rampart protrudes from said substrate and has overhanging portion projecting in a direction parallel to said substrate.

10 8. The method as claimed in claim 1, wherein further comprising (K) depositing organic electroluminescent media to the exposed area between said ramparts on said substrate or said first electrodes; and

15 (L) forming a plurality of second electrodes on said organic electroluminescent media on said substrate or said first electrodes.

10. The method as claimed in claim 1, wherein said first electrodes are perpendicular to said second electrodes.

11. The method as claimed in claim 1, wherein said substrate is transparent.

20 12. The method as claimed in claim 1, wherein further comprising forming a plurality of auxiliary electrodes on or beneath the surface of said substrate before forming a plurality of said first electrodes on said substrate.

25 13. An OLED panel, comprising:

a substrate;

a plurality of first electrodes in parallel stripes, said first electrodes locating on the surface of said substrate;

5 a plurality of anti-glare polyimide pixel-defining layers, said anti-glare polyimide pixel-defining layers selectively locating on said substrate or on said first electrodes, and said anti-glare polyimide pixel-defining layers comprising at least (1) non-photosensitive polyimide or polyimide precursor and (2) light-absorbing pigments or dyes;

10 a plurality of photoresist ramparts, said photoresist ramparts selectively locating on said first electrodes or on said pixel-defining layer;

15 a plurality of organic electroluminescent media, said organic electroluminescent media locating in the exposed area between said ramparts on said substrate; and

 a plurality of second electrodes, said second electrodes locating on said organic electroluminescent media;

 wherein each said ramparts protruding from said substrate and having an overhanging portion projection in a direction parallel to said substrate; and said photoresist ramparts are formed through coating a compositions of photoresist on said substrate, exposing said substrate to masked radiation and development.

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14. The OLED panel as claimed in claim 13, wherein said photoresist ramparts have T-shape cross-section.

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15. The OLED panel as claimed in claim 13, wherein said polyimide pixel-defining layers are parallel stripes; and said pixel-defining stripes intersect with said first electrodes perpendicularly.

5 16. The OLED panel as claimed in claim 15, wherein said photoresist ramparts intersect with said first electrodes perpendicularly.

17. The OLED panel as claimed in claim 13, wherein said photoresist is positive photoresist.

10 18. The OLED panel as claimed in claim 13, wherein said first electrodes are perpendicular to said second electrodes.

19. The OLED panel as claimed in claim 13, wherein said first electrodes are transparent.

20. The OLED panel as claimed in claim 13, wherein said substrate are transparent.

15 21. The OLED panel as claimed in claim 13, wherein said substrate has a plurality of auxiliary electrodes on or beneath said surface of said substrate.

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